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Amended Claims

- 1. (withdrawn) A LVTSCR-like structure having one or more diodes formed in a p-well of the structure.
- 2. (currently amended) A method of increasing the holding voltage of an a-LVTSCR structure that includes an n-well and a p-well formed in a substrate, an n+ region and a p+ region formed in the n-well, and an n+ region and a p+ region formed in the p-well, the method comprising forming at least one additional p+ region and at least one additional n+ region inside a the p-well of the structure to define at least one p-n junction between the p-type material of the p-well and one of the p+ regions, and the n-type material of and at least one of the n+ regions in the p-well, the p-n junction being that is forward biased during normal operation by having said p+ region located on the high voltage side of said at least one n+ region.
- (currently amended) A method of increasing the holding voltage of a an
 LVTSCR structure having an anode in an n-well and a cathode in a p-well, the
 cathode being defined by an n+ region and a p+ region, comprising

forming at least one additional n+ region and at least one additional p+ region in the p-well to define at least one forward biased diode in the p-well, thereby providing an alternative current path from anode to cathode through said at least one diode.

- 4. (original) A method of claim 3, wherein the alternative current path defines a lower resistance current path than the p-well.
- 5. (canceled)
- 6. (canceled)
- 7. (canceled)
- 8. (canceled)